

ABSTRACT

Disclosed is an exposure method and apparatus, an exposure mask and a device
5 manufacturing method, wherein a first surface of a light blocking member having a plurality of openings formed in a mutually adjoining relation is placed at an exposure object side, and light is projected to the light blocking member from its
10 second surface side so that exposure of the exposure object is carried out on the basis of near field light leaking from the openings. For exposure, interference is caused between surface plasmon polariton waves passing respectively
15 through adjacent openings and going around to the first surface side, and, on the basis of it, a portion having a decreased light intensity is produced in the exposure object so that the exposure is carried out by use of the decreased
20 light intensity portion.